

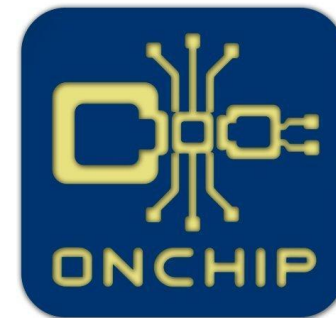
Lecture 01: Metal-Oxide-Semiconductor Field Effect Transistor (MOSFET)

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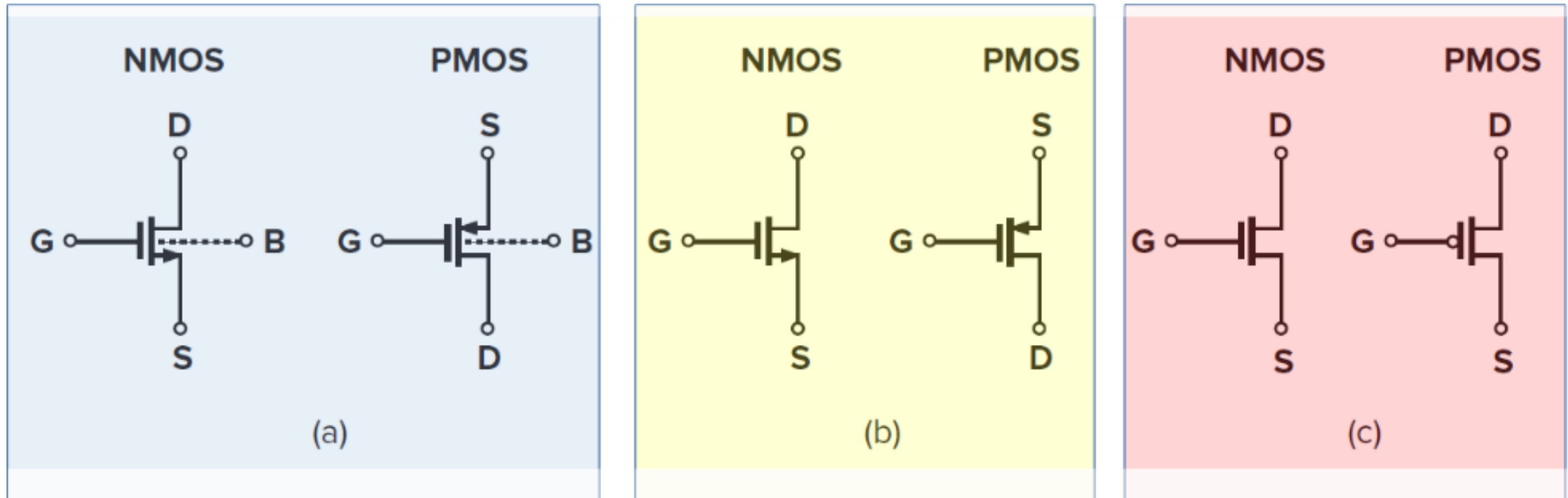


Outline

Remember this is an overview*

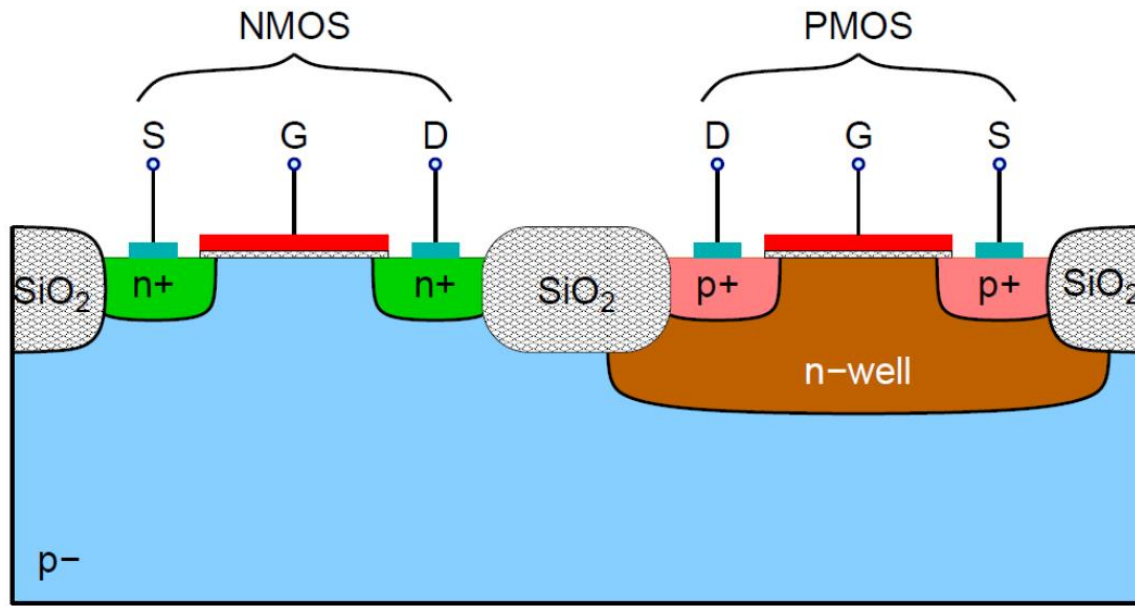
- Introduction
- Basic Operation
- Regions
 - Triode
 - Saturation
- Summary

MOSFET Circuits Symbols

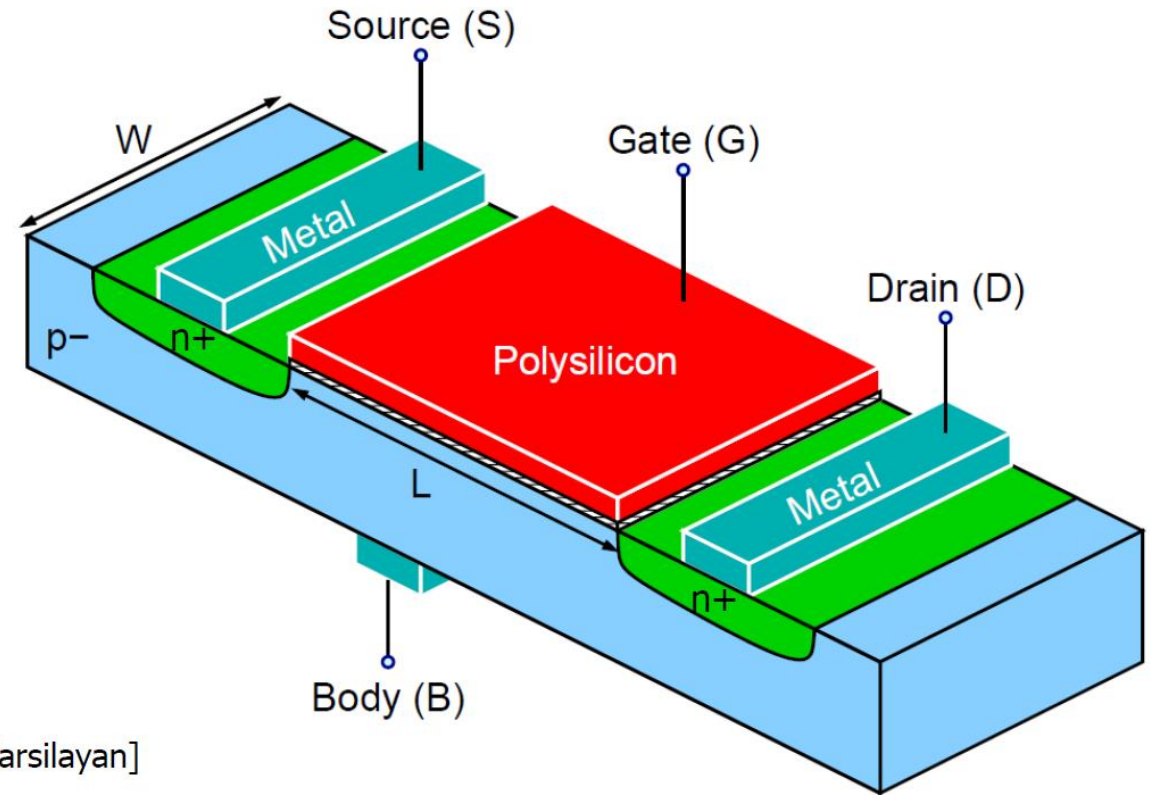


- MOSFETs are 4-terminal devices: Drain, Gate, Source, and Body (or Bulk)
- Body terminal generally has small impact in normal operation.
- Two complementary types: **NMOS** and **PMOS**

MOSFET Physical Structure



[Karsilayan]

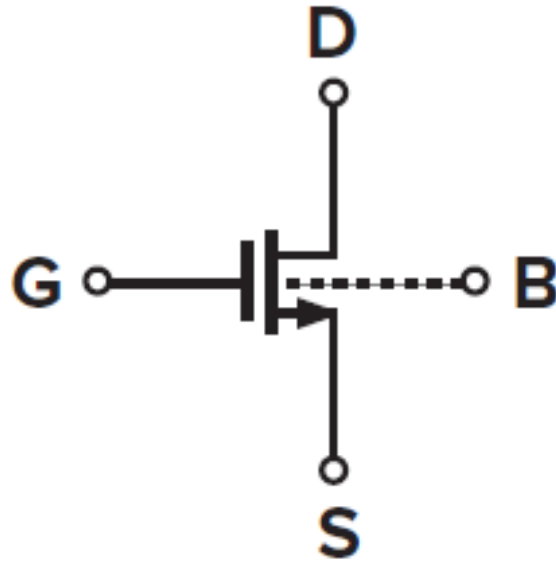


[Karsilayan]

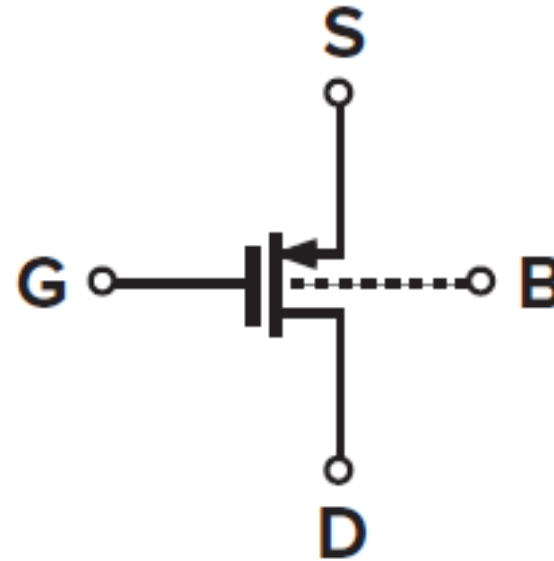
- MOSFET is a symmetrical device (integrated)

MOSFET – Initial Thoughts

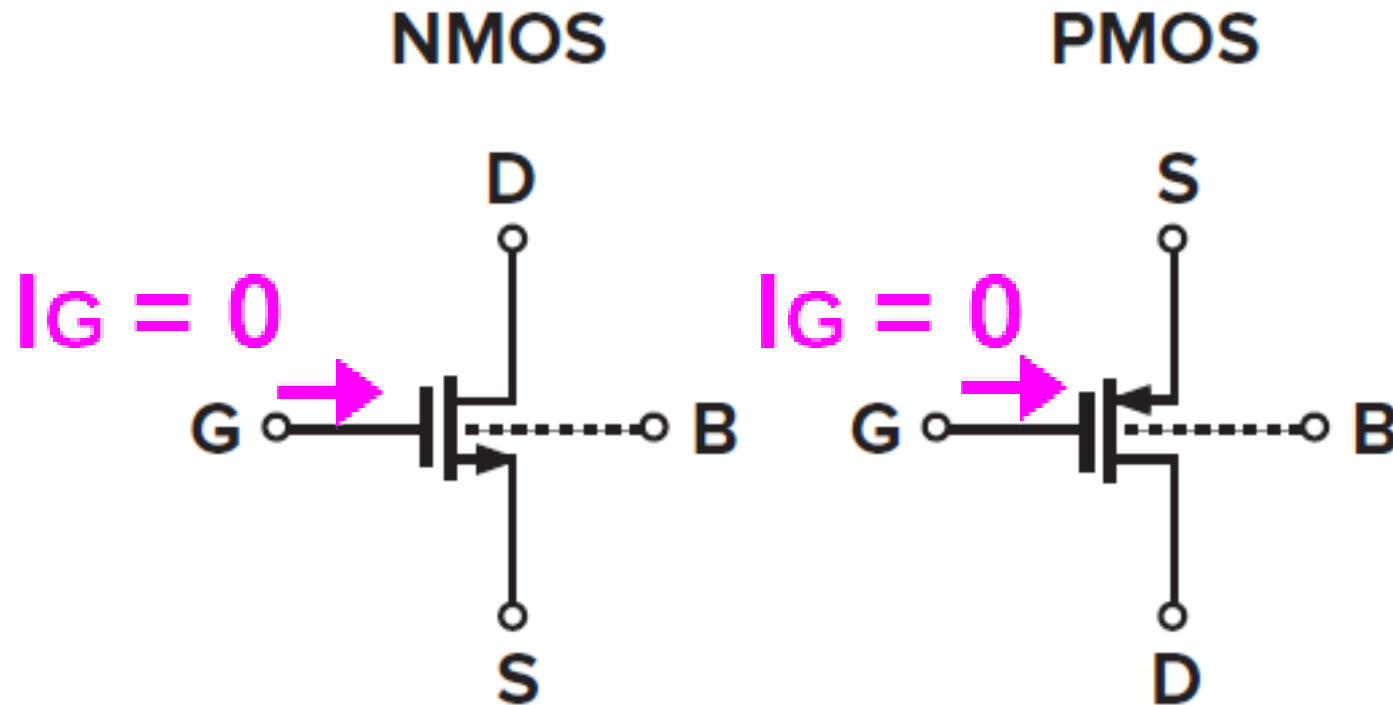
NMOS



PMOS



MOSFET – Initial Thoughts



- The current flowing through Gate terminal can be considered equal to zero.

MOSFET – Initial Thoughts

In NMOS:

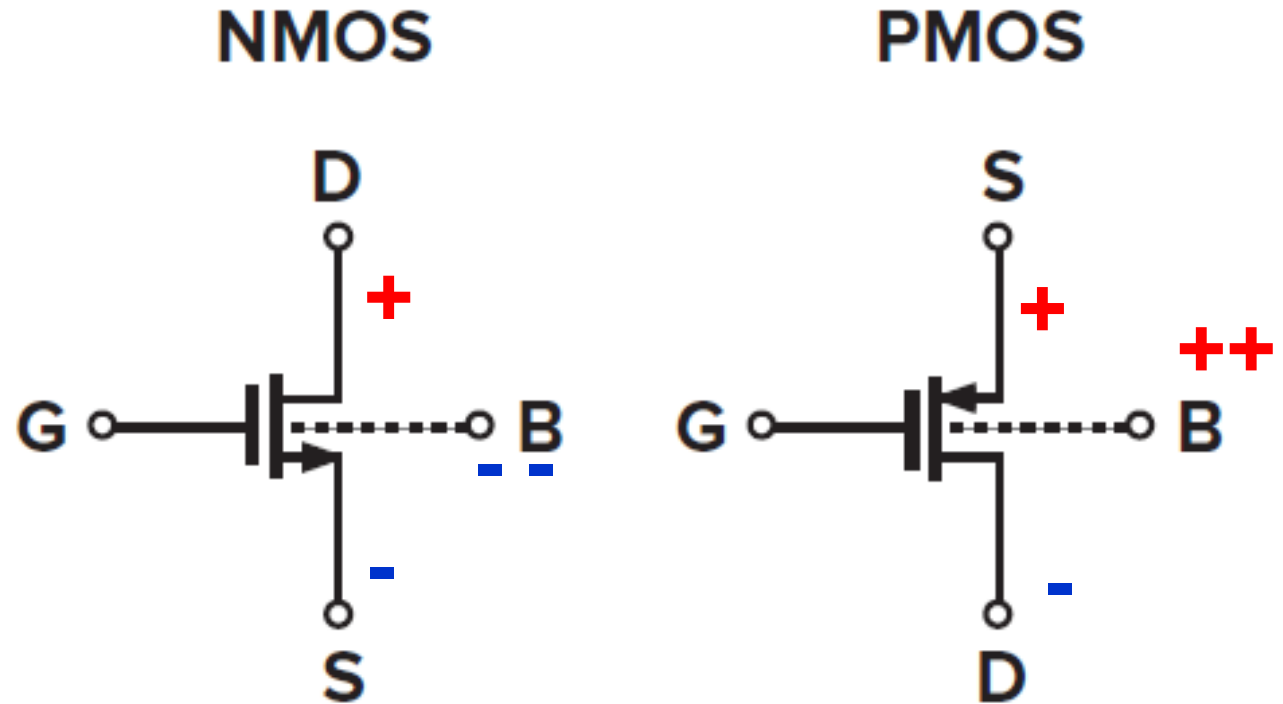
Drain more **+** than **source**.

Bulk (body) must be connected to the most **-** terminal in the circuit (or source).

In PMOS:

Source is more **+** than **drain**.

Bulk (body) must be connected to the most **+** terminal in the circuit (or source).



MOSFET – Initial Thoughts

In NMOS:

Drain more + than **source**.

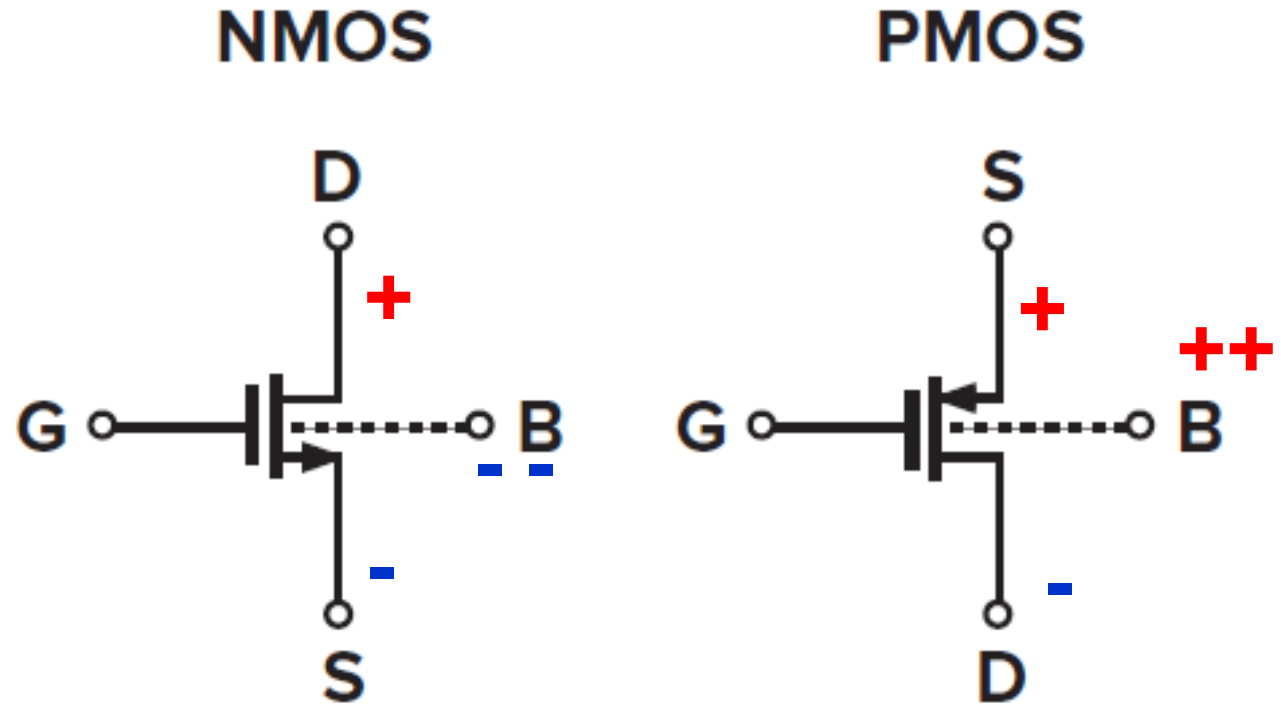
Bulk (body) must be connected to the most - terminal in the circuit (or source).

In PMOS:

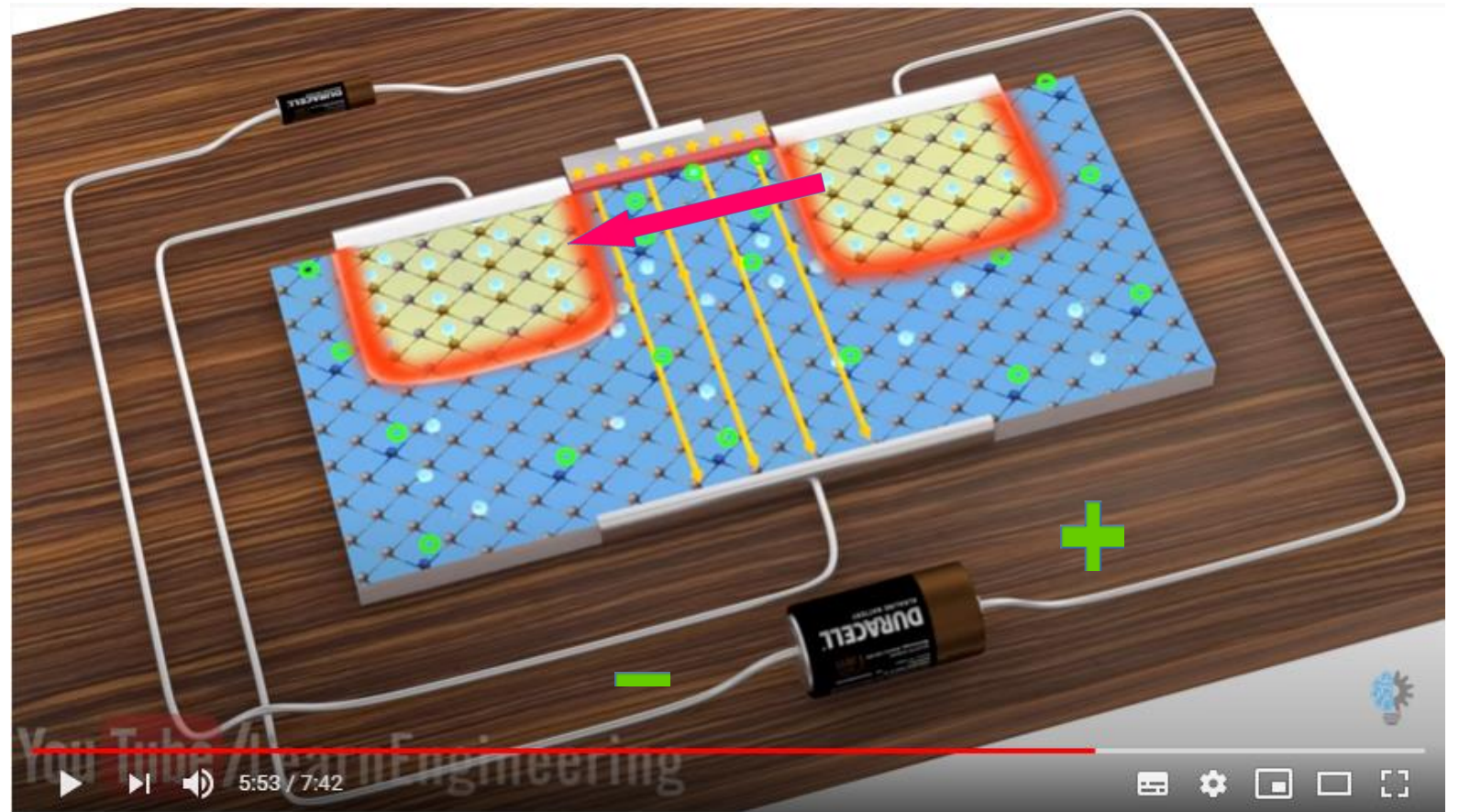
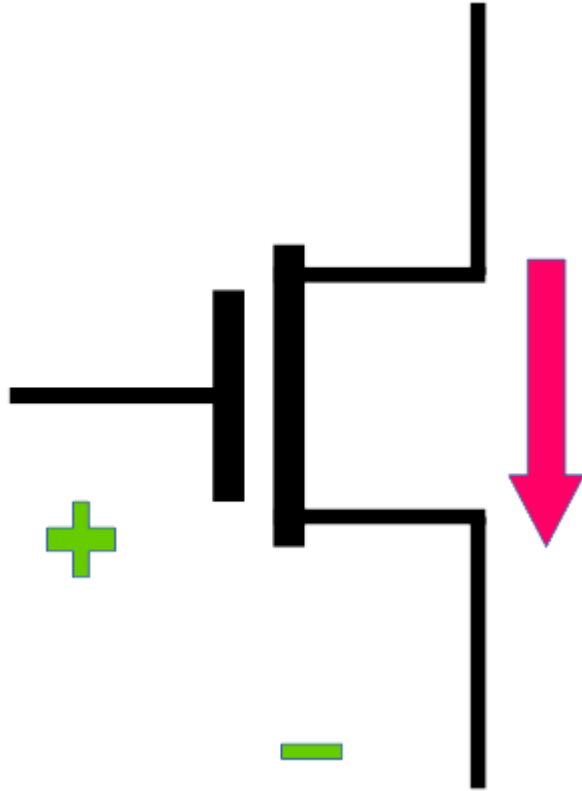
Source is more + than **drain**.

Bulk (body) must be connected to the most + terminal in the circuit (or source).

Bulk also can be connected to source □ **Why?**

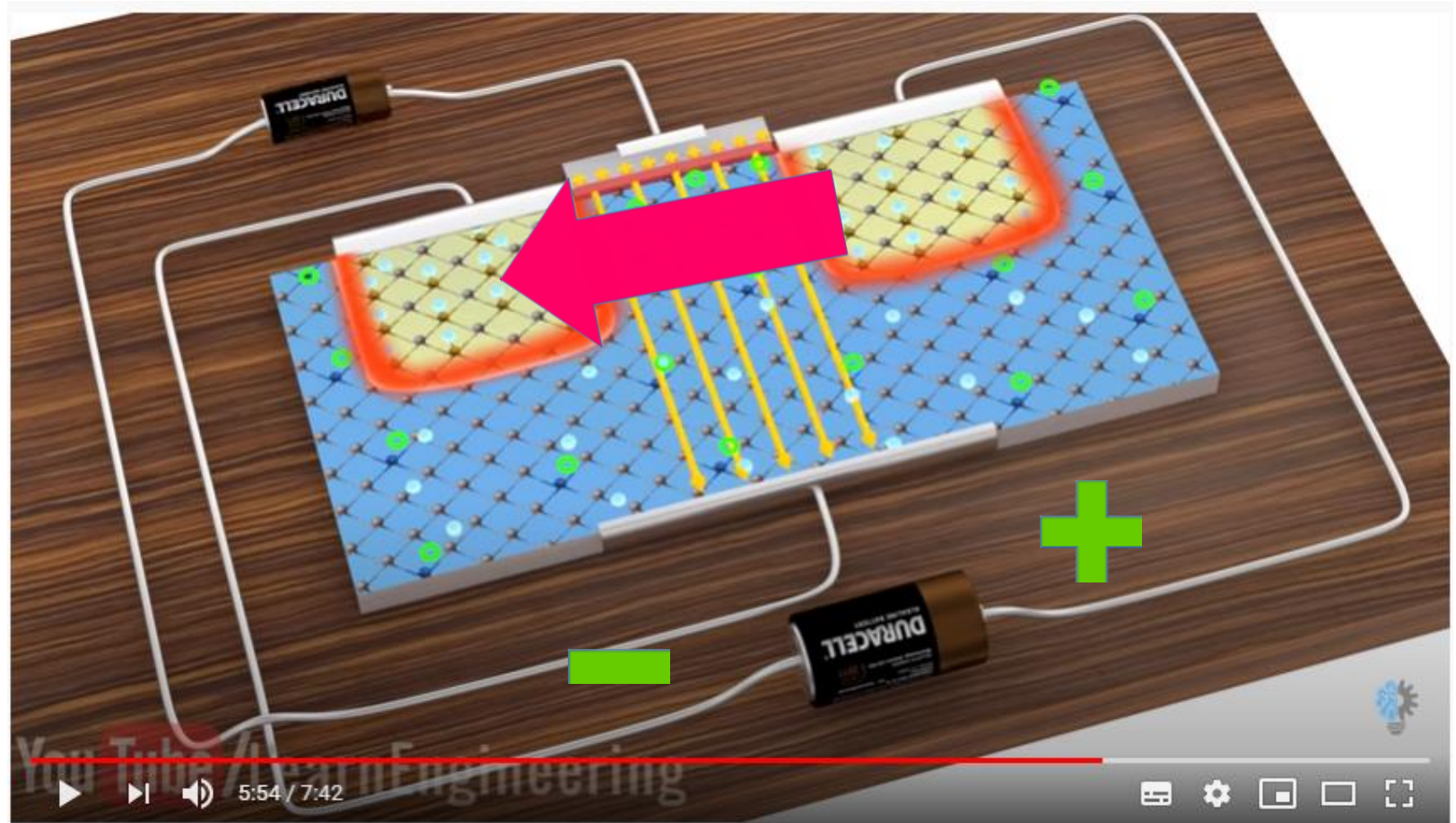
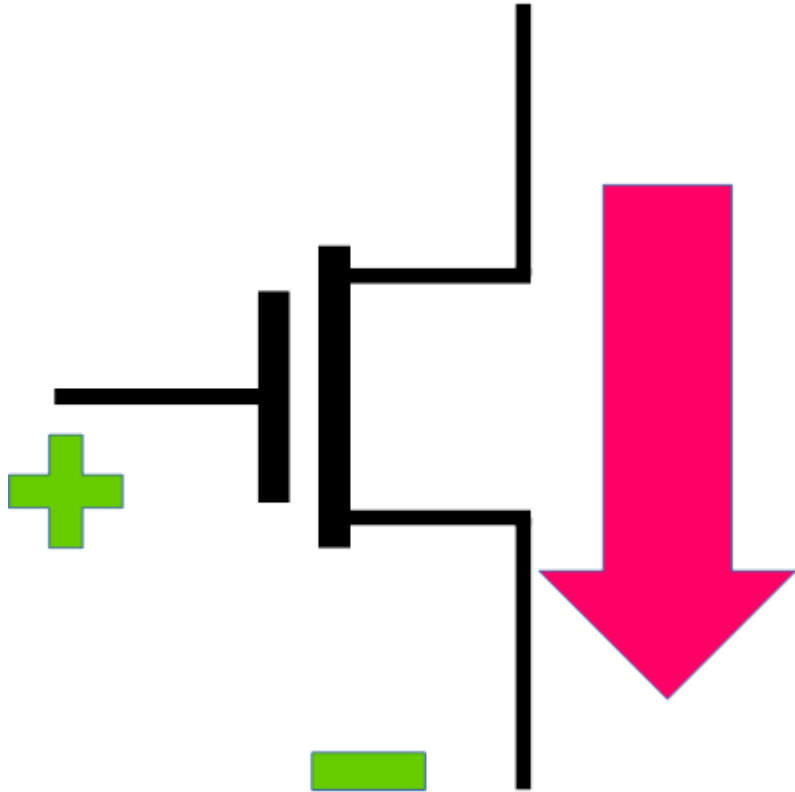


MOSFET – Initial Thoughts



- MOSFET is ON
- In red the conventional current (positive charge)

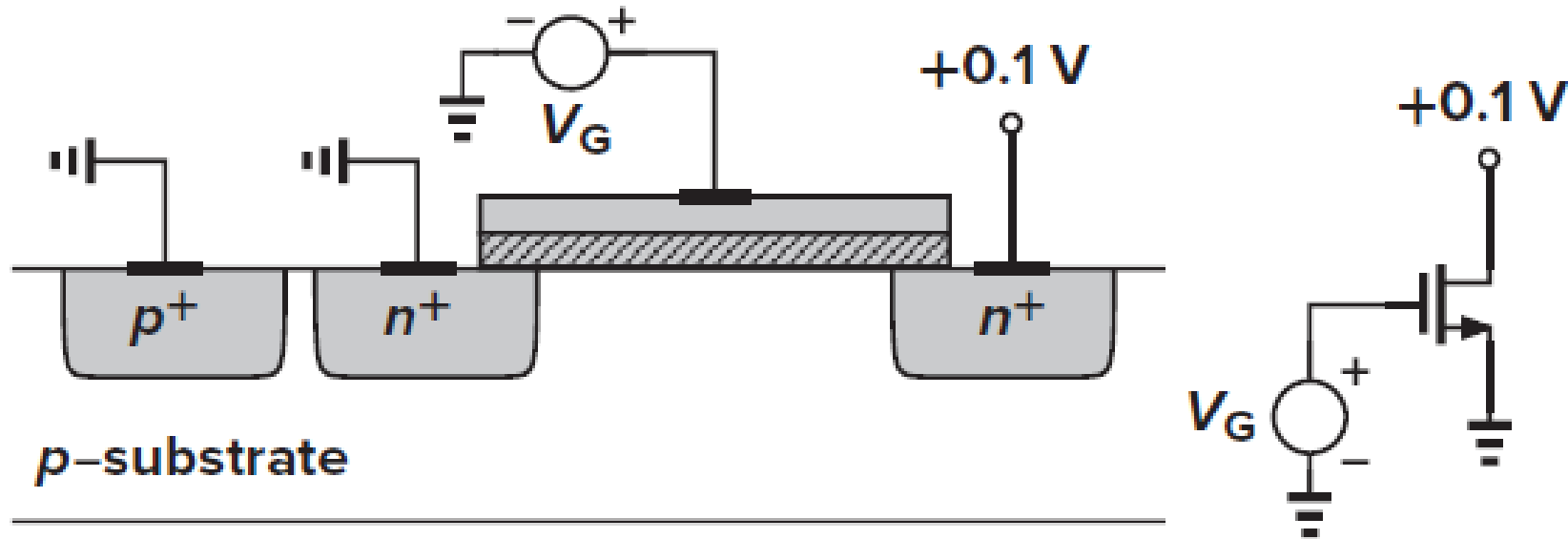
MOSFET – Initial Thoughts



- MOSFET is ON
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MOSFET – I/V Characteristics: NMOS

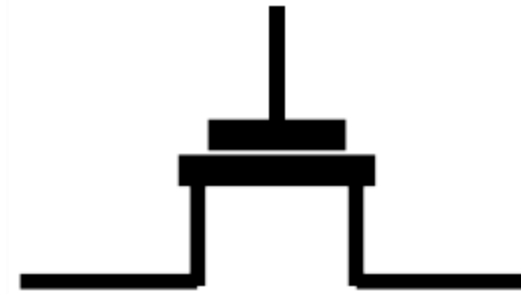
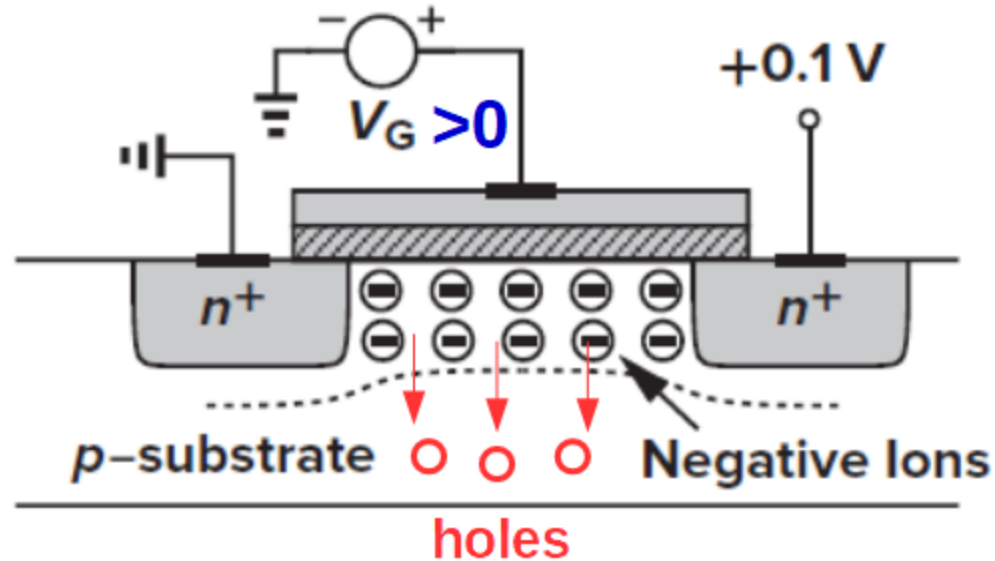
- The Threshold Voltage



- We need to TURN ON the device ☐ If $V_G = 0$, there is no current flowing through the device (Between which terminals?)

MOSFET – I/V Characteristics: NMOS

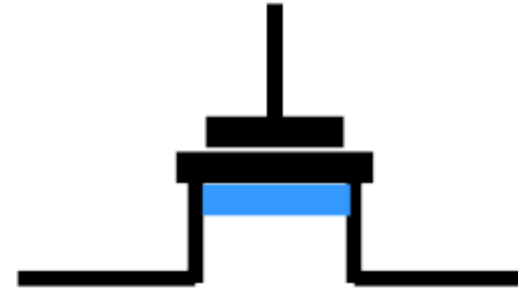
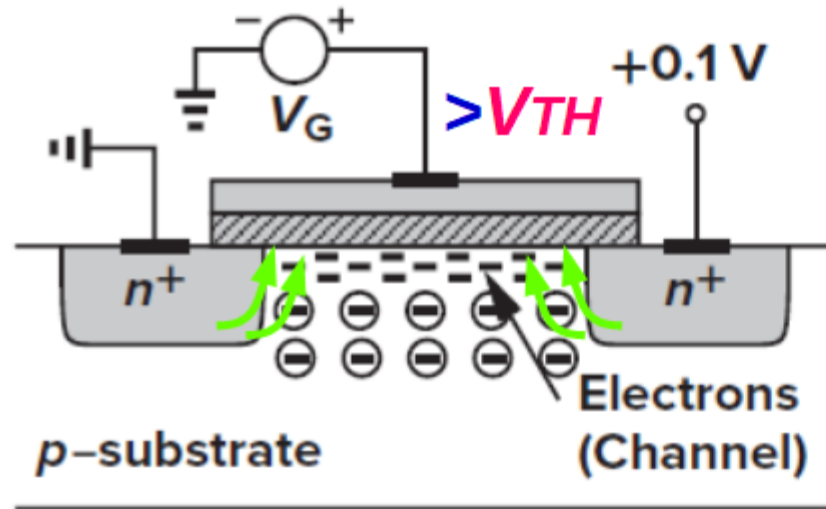
- The Threshold Voltage



- As V_G becomes more positive, the holes in the p -substrate are repelled from the gate area, leaving negative ions behind so as to mirror the charge on the gate. **No current flows!**

MOSFET – I/V Characteristics: NMOS

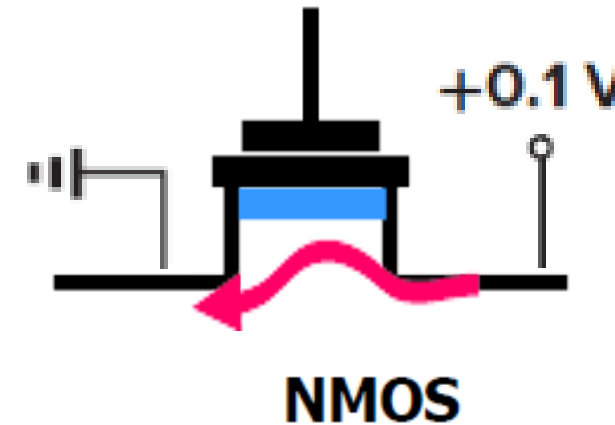
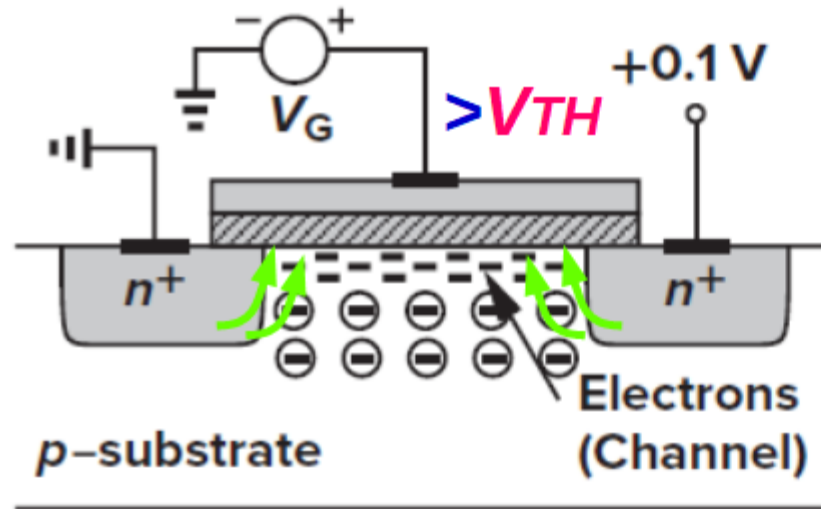
- The Threshold Voltage



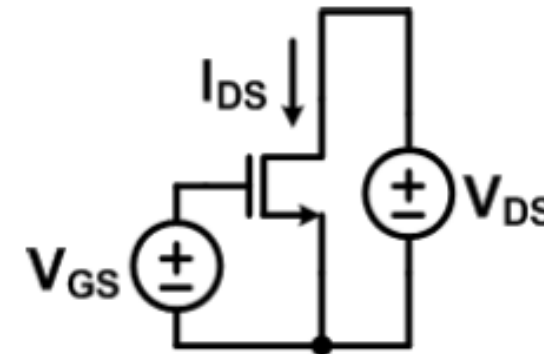
When V_G becomes a sufficient positive value, electrons flow from the diffusions and create a “channel interface”. This value is the “threshold voltage” $\rightarrow V_{TH}$

MOSFET – I/V Characteristics: NMOS

- The Threshold Voltage



- Now a current flow is possible!!!
- Check the convention



MOSFET – I/V Characteristics: NMOS

$$I = Q_d \cdot v$$

$$Q_d = WC_{ox}(V_{GS} - V_{TH})$$

$$Q_d(x) = WC_{ox}[V_{GS} - V(x) - V_{TH}]$$

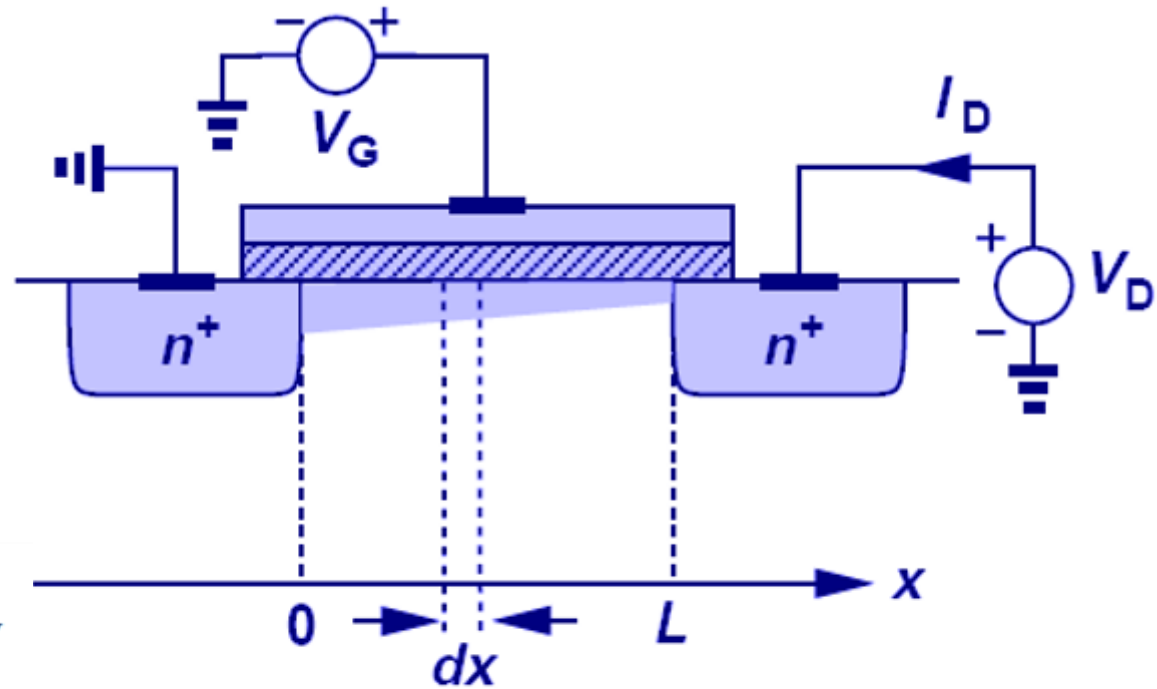
$$I_D = -WC_{ox}[V_{GS} - V(x) - V_{TH}]v$$

$$v = -\mu_n E = +\mu_n \frac{dV}{dx},$$

$$I_D = WC_{ox}[V_{GS} - V(x) - V_{TH}]\mu_n \frac{dV(x)}{dx}$$

$$\int_{x=0}^L I_D dx = \int_{V=0}^{V_{DS}} WC_{ox}\mu_n[V_{GS} - V(x) - V_{TH}]dV$$

$$I_D = \mu_n C_{ox} \frac{W}{L} \left[(V_{GS} - V_{TH})V_{DS} - \frac{1}{2}V_{DS}^2 \right]$$

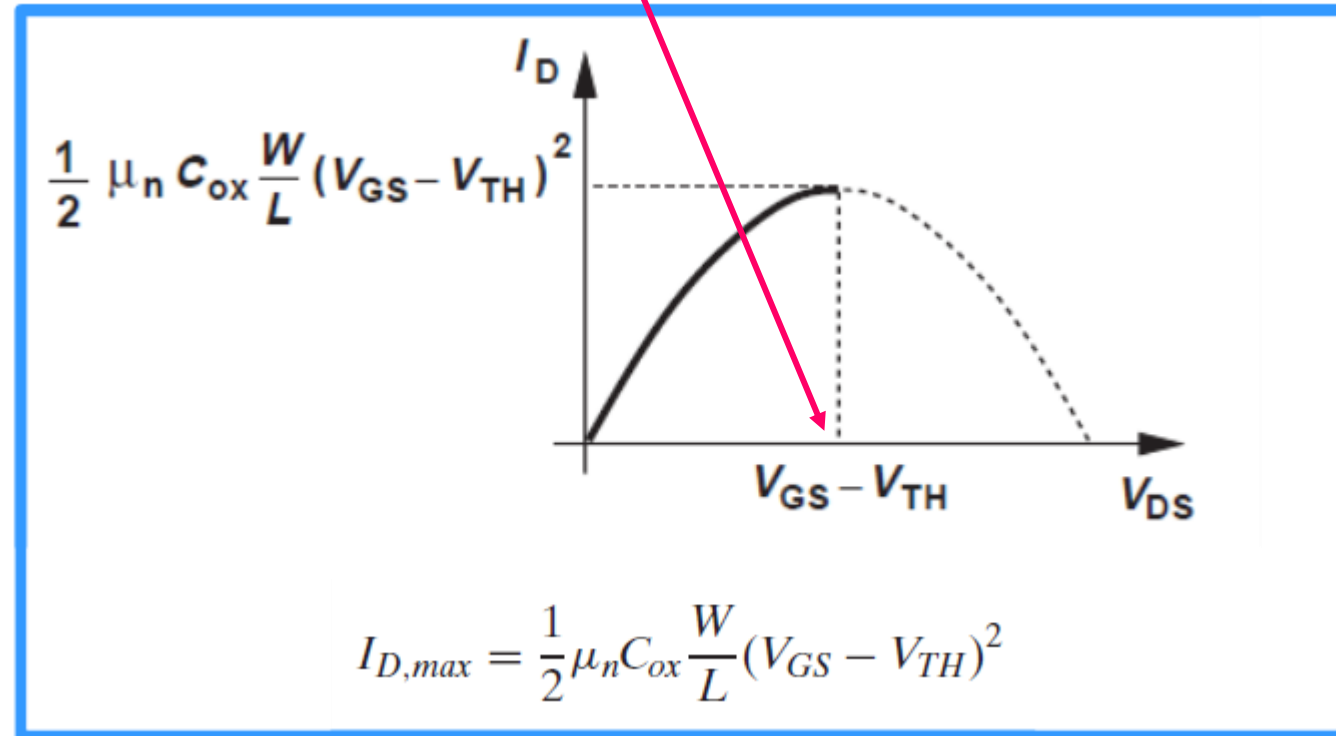


$$Q(x) = WC_{ox}[V_{GS} - V(x) - V_{TH}]$$

[Razavi]

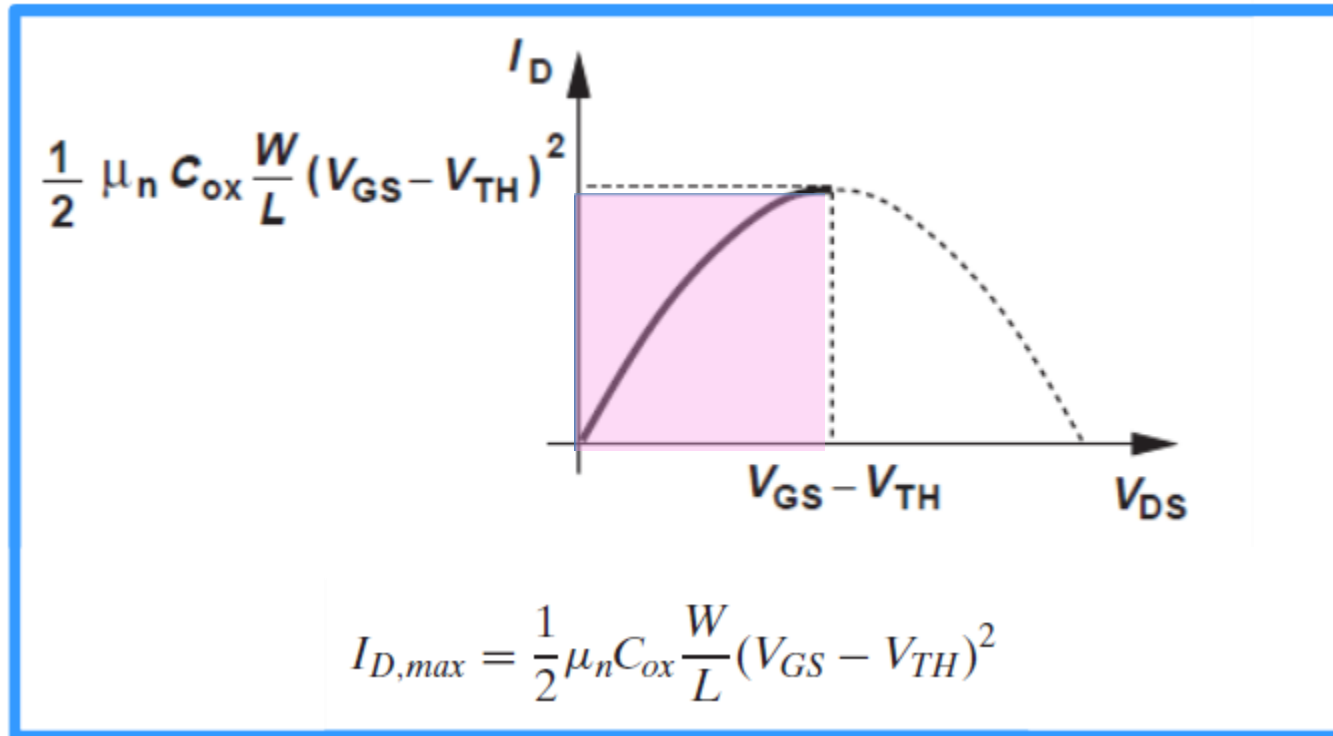
MOSFET – I/V Characteristics: NMOS

- Maximum current happens at $(V_{GS} - V_{TH})$, called the “overdrive voltage”



MOSFET – I/V Characteristics: NMOS

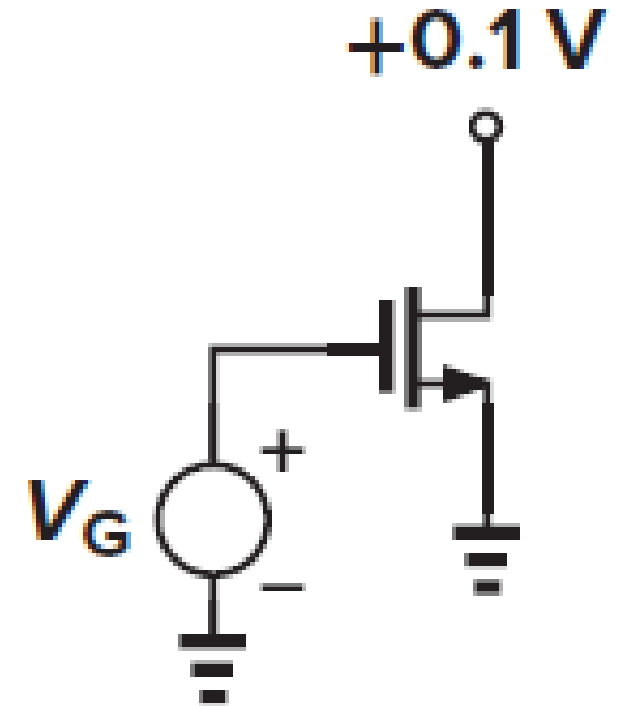
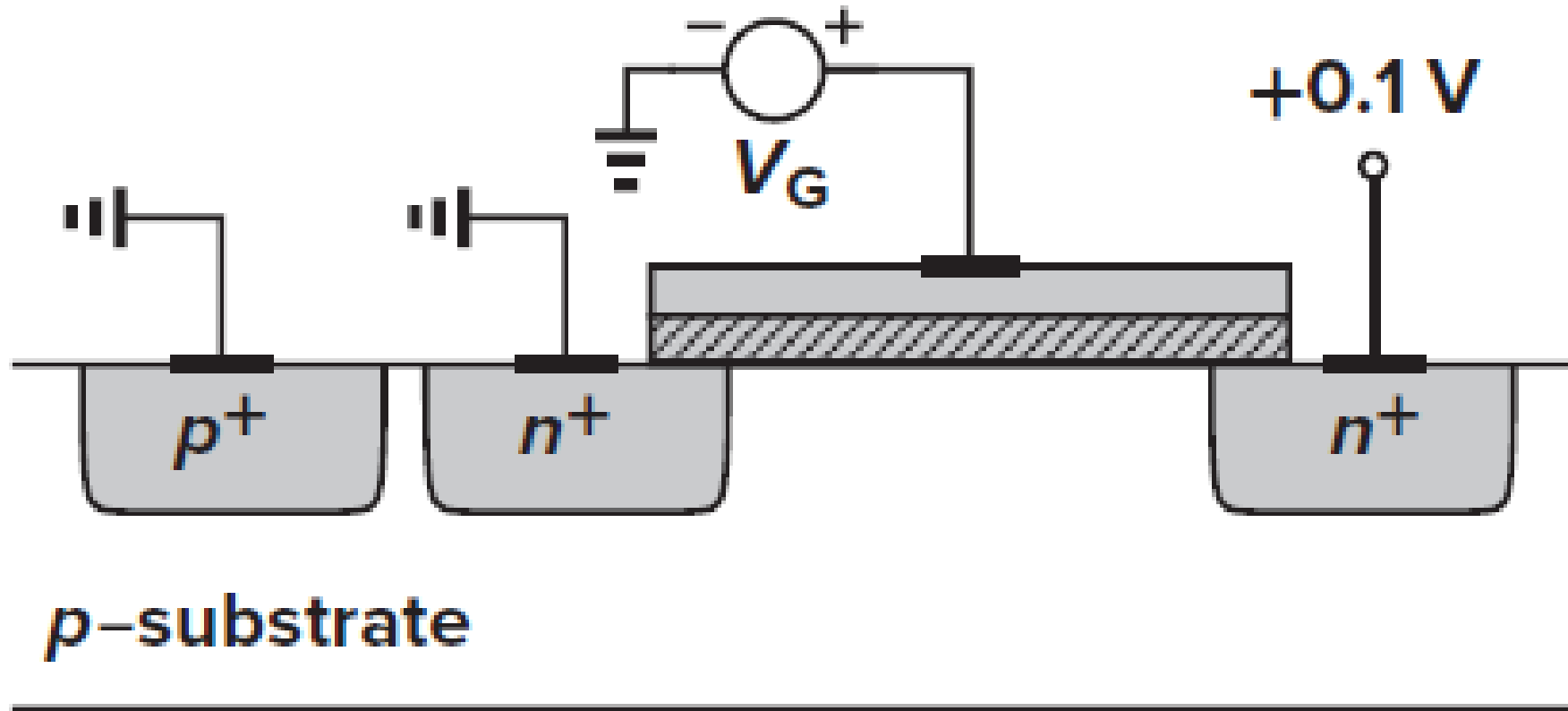
- Maximum current happens at $(V_{GS} - V_{TH})$, called the “overdrive voltage”



This is known
as the TRIODE
region

MOSFET – Triode Region

- MOSFET looks like a controllable resistance

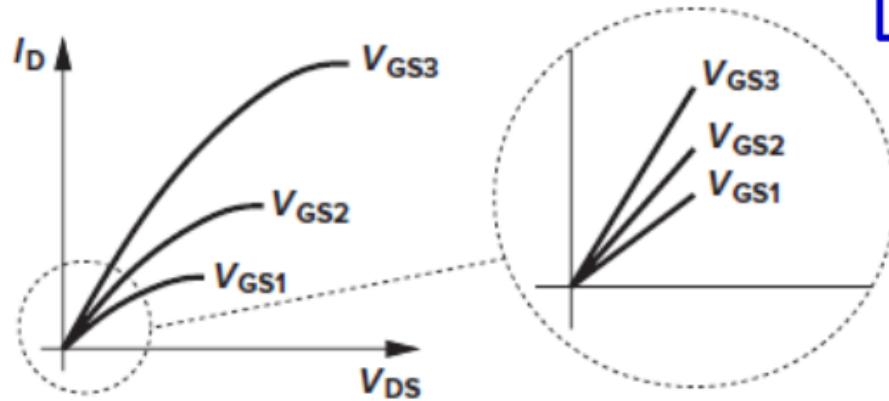


MOSFET – Triode Region

- For low V_{DS} values, the channel is still homogeneous
- For higher V_{DS} values, the behavior becomes more and more nonlinear

MOSFET – Triode Region

- For low V_{DS} values, the channel is still homogeneous



$$I_D = \mu_n C_{ox} \frac{W}{L} \left[(V_{GS} - V_{TH}) V_{DS} - \frac{1}{2} V_{DS}^2 \right]$$

$$V_{DS} \ll 2(V_{GS} - V_{TH})$$

$$I_D \approx \mu_n C_{ox} \frac{W}{L} (V_{GS} - V_{TH}) V_{DS}$$

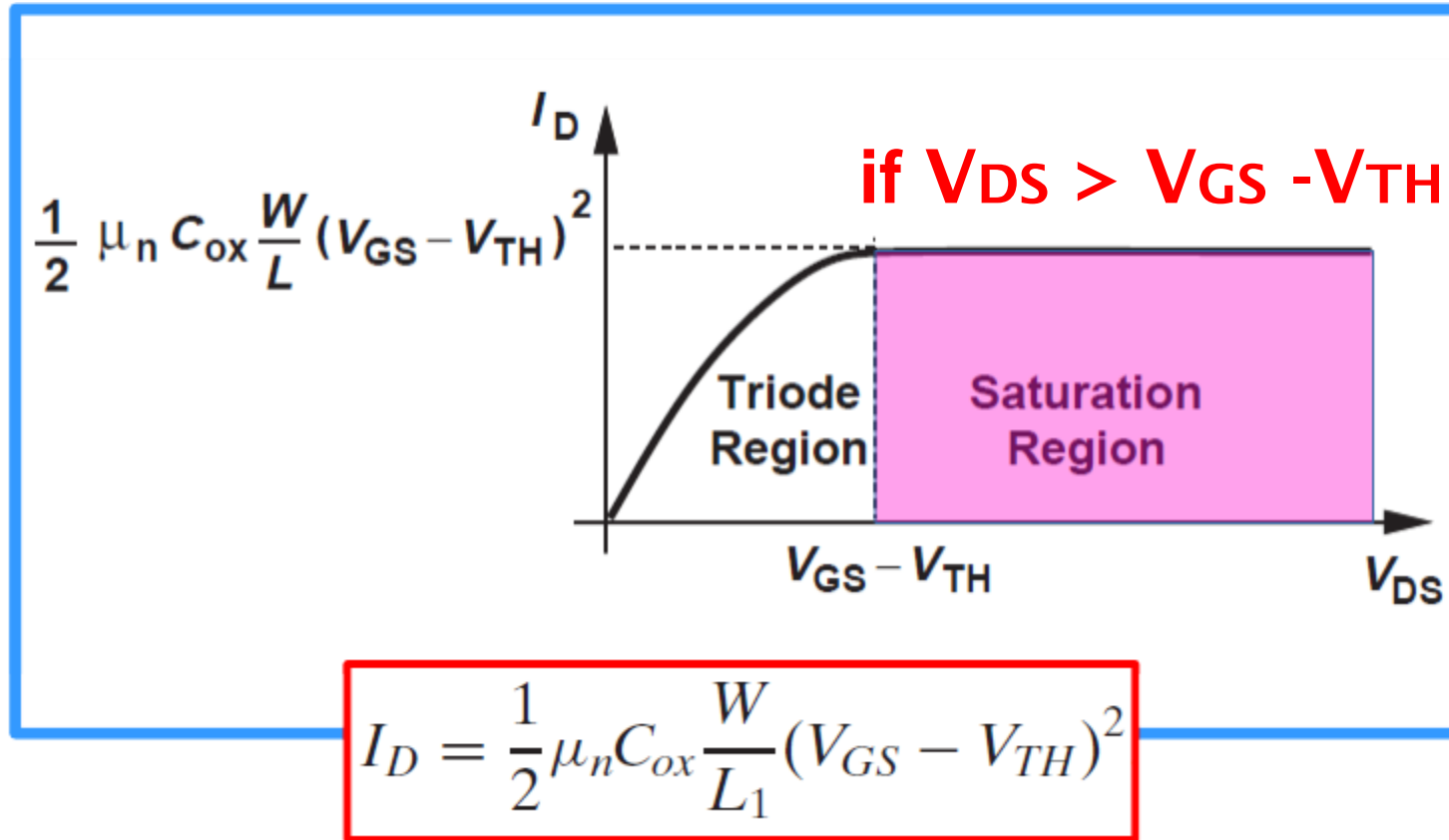
$$R_{on} = \frac{1}{\mu_n C_{ox} \frac{W}{L} (V_{GS} - V_{TH})}$$

MOSFET – Triode Region

- For low V_{DS} values, the channel is still homogeneous
- For higher V_{DS} values, the behavior becomes more and more nonlinear

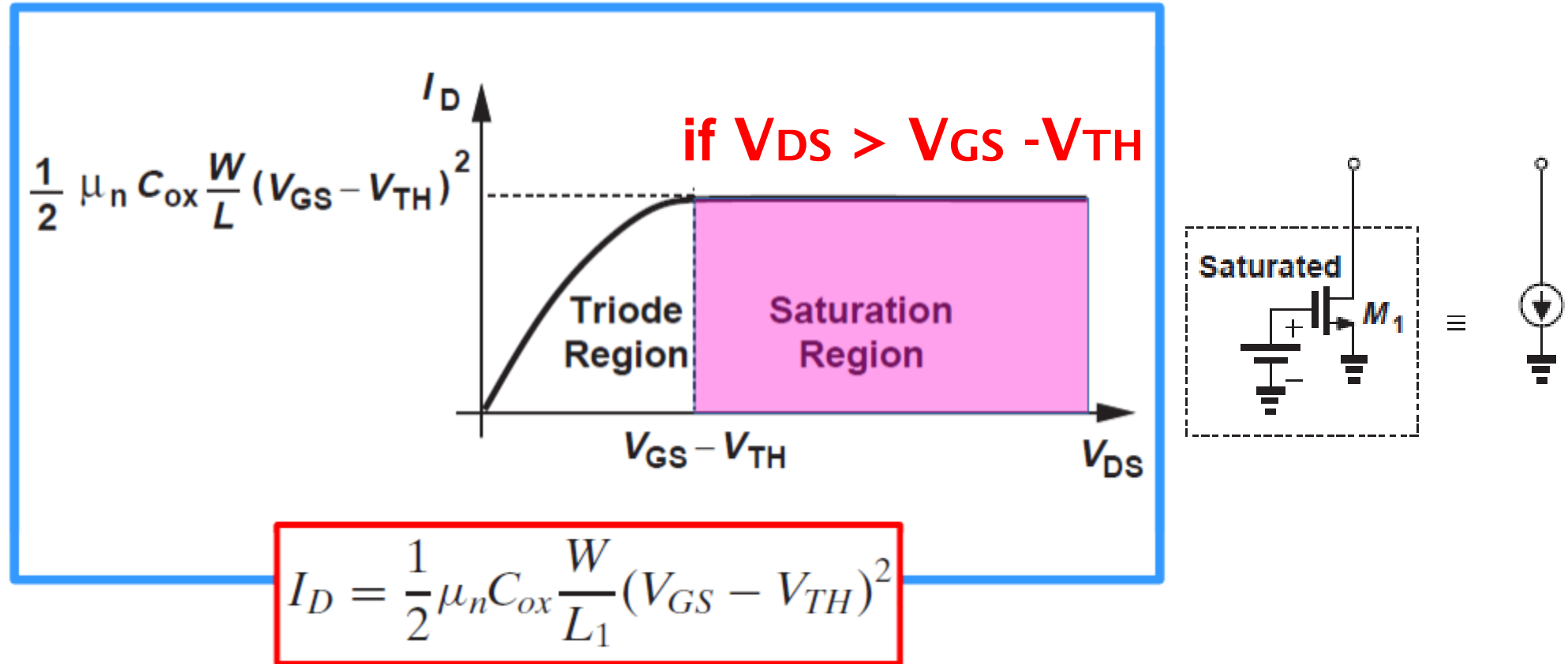
MOSFET – Saturation Region

- For higher V_{DS} values, the behavior becomes more and more nonlinear

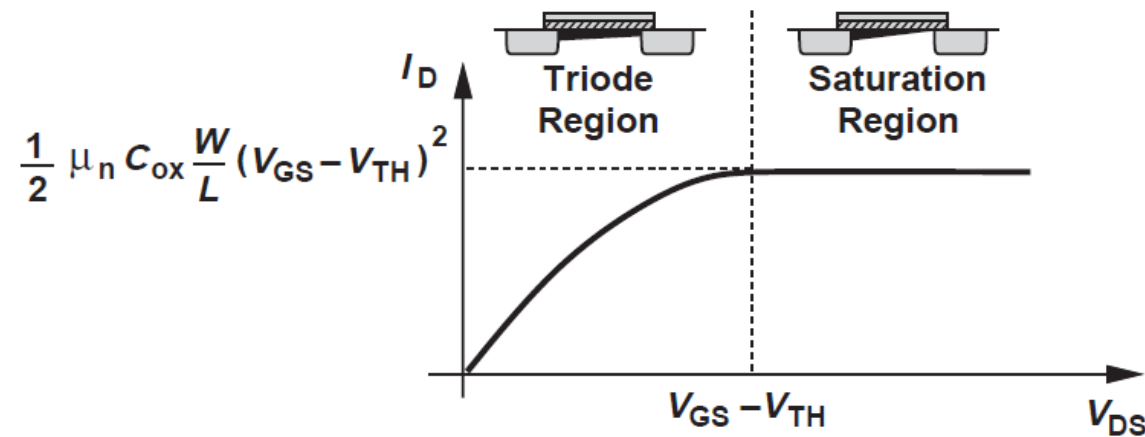


MOSFET – Saturation Region

- For higher V_{DS} values, the behavior becomes more and more nonlinear



MOSFET – 1st Arrival: Summary



TURN ON the Device
 $V_{GS} > V_{TH}$

Triode Region

- $V_{DS} < V_{GS} - V_{TH}$
- I_D depends on V_{GS} and V_{DS}

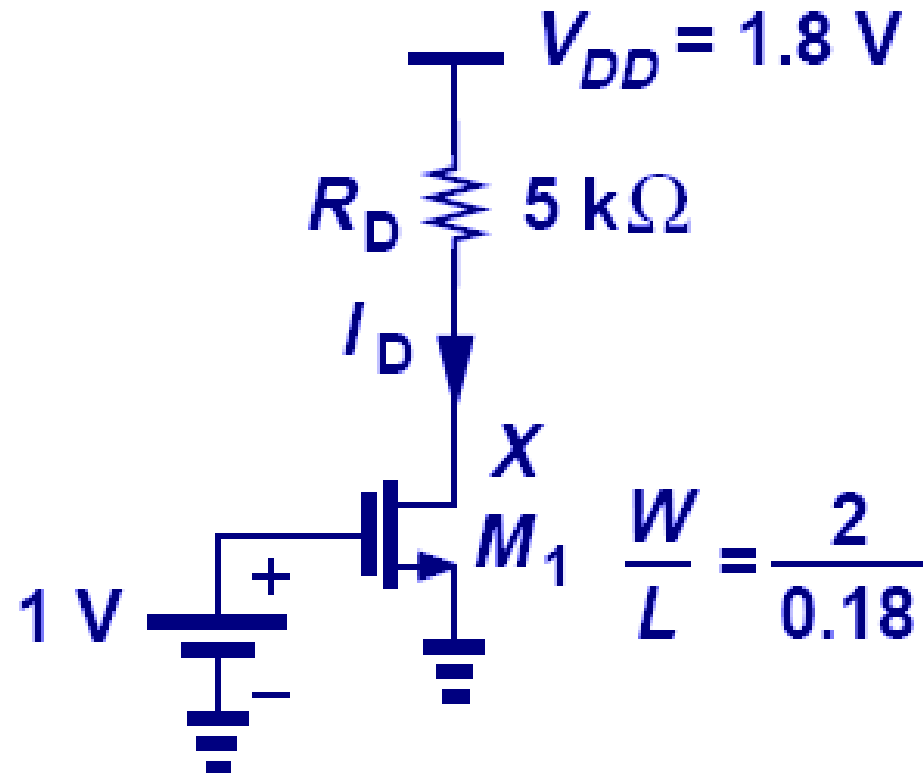
$$I_D = \mu_n C_{ox} \frac{W}{L} \left[(V_{GS} - V_{TH}) V_{DS} - \frac{1}{2} V_{DS}^2 \right]$$

Saturation Region

- $V_{DS} \geq V_{GS} - V_{TH}$
- I_D depends on V_{GS} (mostly)

$$I_D = \frac{1}{2} \mu_n C_{ox} \frac{W}{L_1} (V_{GS} - V_{TH})^2$$

Let's Practice!



Calculate the bias current of M1. Assume.

$$\mu_n C_{ox} = 100\text{ uA/V}^2$$

$$V_{TH} = 0.4\text{ V}$$

What is the operation region?

How can check our answers?

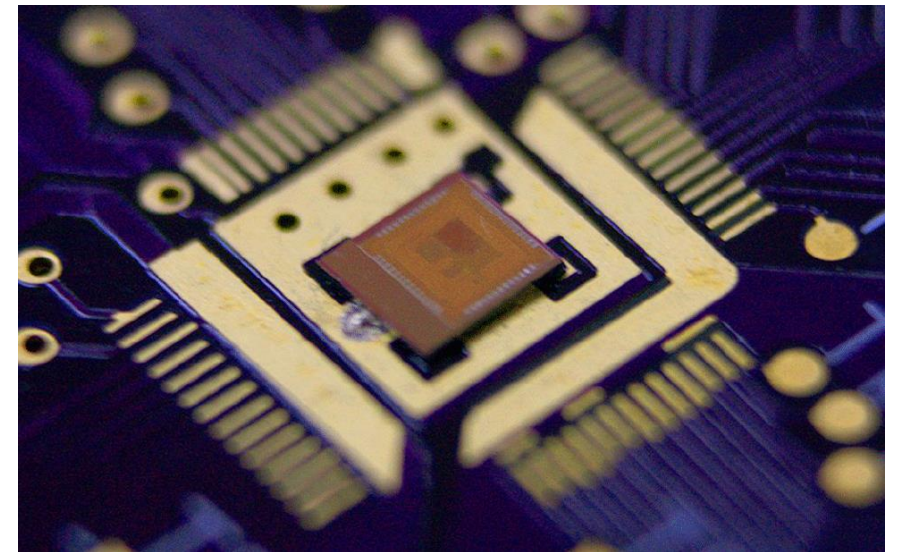
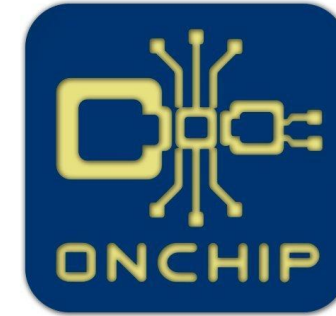
Homework

- PMOS Case Study
- Complementary Reading ☐ Hand Notes
- Think and choose the best question you have after homework and prepare it for the next class

Thanks



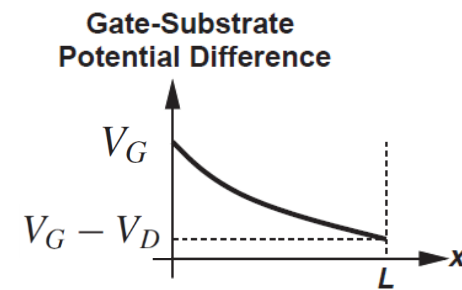
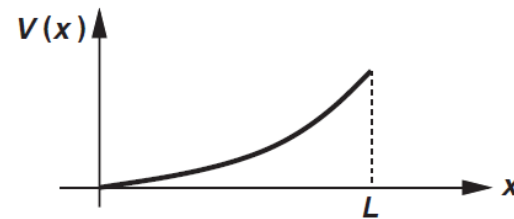
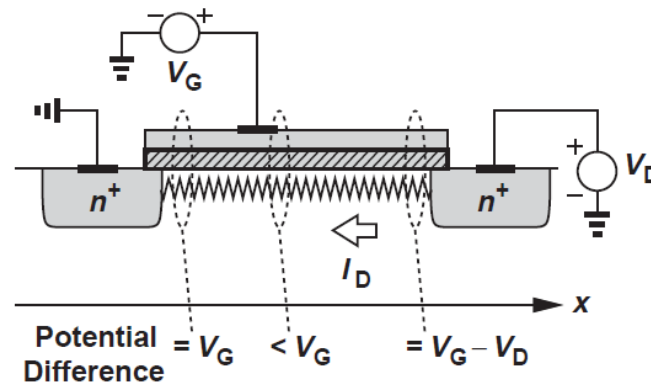
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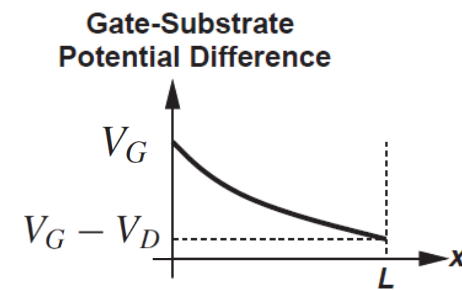
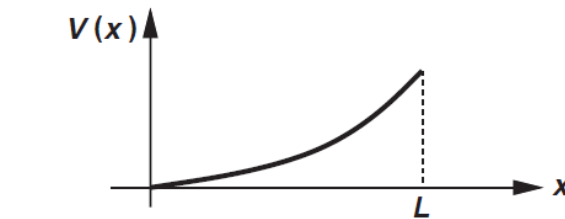
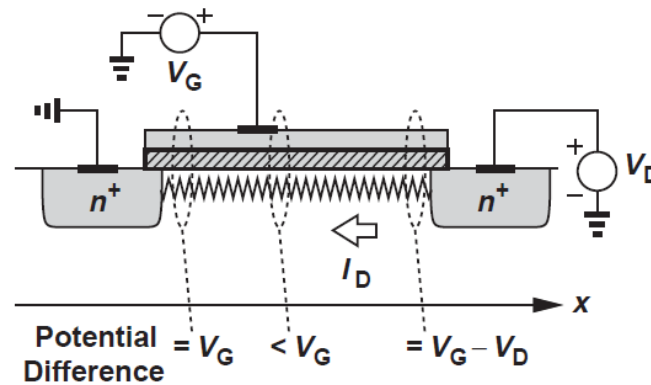
Appendix

- Saturation occurs due to a phenomenon known as **Channel Pinch-Off**. Let's try to understand!



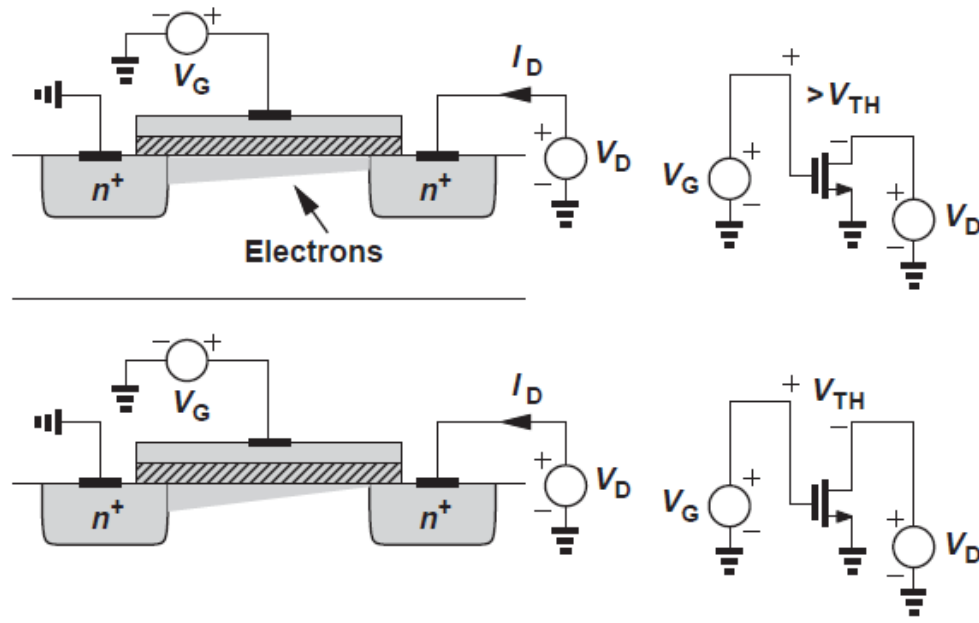
Why this happen?

- Saturation occurs due to a phenomenon known as **Channel Pinch-Off**. Let's try to understand!



MOS I/V Characteristics

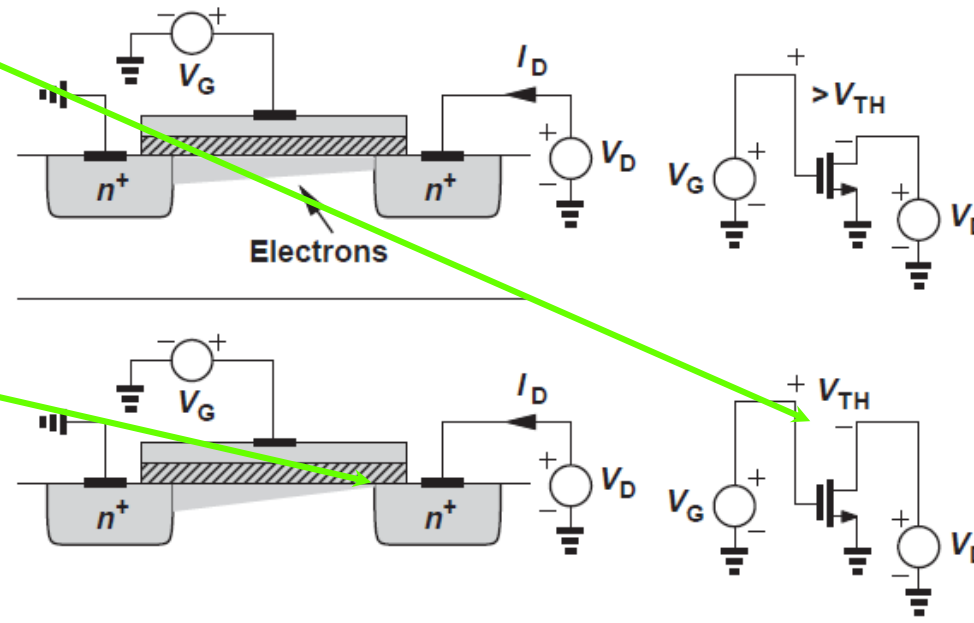
- Density of electrons falls to a minimum at $x=L$
- If drain voltage is high enough to produce
- $V_G - V_D < V_{TH}$, then the channel ceases to exist near the drain



MOS I/V Characteristics

- Density of electrons falls to a minimum at $x=L$
- If drain voltage is high enough to produce
- $V_G - V_D < V_{TH}$, then the channel ceases to exist near the drain

We say at this point
that channel is
“pinched off”



The saturation current

- The current integral has to be adjusted

$$\int_{x=0}^{x=L_1} I_D dx = \int_{V(x)=0}^{V(x)=V_{GS}-V_{TH}} \mu_n C_{ox} W [V_{GS} - V(x) - V_{TH}] dV.$$

$$I_D = \frac{1}{2} \mu_n C_{ox} \frac{W}{L_1} (V_{GS} - V_{TH})^2$$

This is the saturation current